	L Number	Hits	Search Text	DB	Time stamp
### 2003/09/09 10: ### 2003/09/0	1	0	\$fluoroadamantyl adj (methacrylate acrylate)	USPAT;	2003/09/09 10:03
1   SiluoroSadamantyl adj (methacrylate acrylate)   2003/09/09 10: acryla	.\				
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997   100005691 adj (methacrylate acrylate)   12003/09/09 12: 0003/09/09/09/09/09/09/09/09/09/09/09/09/09/	2	1		1	2003/03/03 10:11
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10   997   fluoroscyl adj (methacrylate acrylate)   USPAT,   2003/09/09 12:   USPAT,   USPAGNUM,   USPAT,   U					
22	9	997	fluoro\$6yl adj (methacrylate acrylate)		2003/09/09 12:04
2	ļ			US-PGPUB;	
22	ł				
("2003103039") or ("6602646") or ("559458")   US-PGPUB;   EPO; JDO;   Or ("2002158085") or ("2001044070") or   EPO; JDO;   DRRWENT   US-PGPUB;   EPO; JDO;   DRRWENT   US-PGPU	_		//	T .	
Or ("2002150835") Or ("2001044070") or ("579569").PN.	8	22			2003/09/09 11:17
("6579659").PN.	1			1	
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11 6 (430/907.ccls. 430/905.ccls.) and (fluoros6yl adj (methacrylate acrylate)) 12 247 (\$10octafluoropentyl adj (methacrylate acrylate)) 13 6995 (methacrylate acrylate)) and (reset) 14 12 (fluorine fluoro fluorinated) same (methacrylate acrylate)) and (reset) 15 905 fluoroalkyl near (methacrylate acrylate) 16 7916 ((\$10octafluoropentyl adj (methacrylate acrylate)) ghotoresist) (\$10fluorinated) same (methacrylate acrylate)) and (reset) 16 7916 ((\$10octafluoropentyl adj (methacrylate acrylate)) ghotoresist)) (cyclo5yl adj (methacrylate acrylate)) ghotoresist) (cyclo5yl adj (methacrylate acrylate)) ghotoresist)) (cyclo5yl adj (methacrylate acrylate)) ghotoresist) (cyclo5yl adj (methacrylate) gept) gept) gept) gept) gept) gept) gept) gept) ghotoresist) (cyclo5yl adj (methacrylate) gept) gept) gept) gept) gept) gept) gept) gept) gept)	10	766		1	2003/09/09 12:04
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(methacrylate acrylate) )) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)  ((((\$10octafluoropentyl adj (methacrylate acrylate))) (\$10fluor\$10adamantyl adj (us-pgpub; (methacrylate acrylate))) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) (fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and		l			
near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.)  ((((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (us-pgpuB; (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and	.	l			
(430/907.ccls. 430/905.ccls.) ((((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (us-pgpub; (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) (fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and		l			
18 66 ((((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (us-pgpub; (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) (fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and		l			*
acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and	18	66		USPAT:	2003/09/09 12:24
(methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.)) and					, >-, +- 10,03
acrylate) ) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )) (fluoroalkyl near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.) and		ļ			
same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )) (fluoroalkyl near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.) and			photoresist) ) (cyclo\$5yl adj (methacrylate		
(methacrylate acrylate) )) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.) and		İ			
near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.) and	İ				
(430/907.ccls. 430/905.ccls.)) not ((430/907.ccls. 430/905.ccls.) and	1				
((430/907.ccls. 430/905.ccls.) and					
	ł				
(fluoroskyl adi (methagrylate agrylate)))	ł	1	((430/907.ccis. 430/905.ccis.) and (fluoro\$6yl adj (methacrylate acrylate)))		

1	`
	_

19	0	2-fluoroadamantyl adj acrylate	USPAT; US-PGPUB; EPO; JPO;	2003/09/09 12:24
			DERWENT	
20	2	2-fluoroadamantyl	USPAT;	2003/09/09 12:25
		•	US-PGPUB;	, , ===
			EPO; JPO;	
			DERWENT	
21	6	\$7fluoroadamantyl	USPAT;	2003/09/09 12:51
			US-PGPUB; EPO; JPO;	
			DERWENT	
22	4	\$7fluoronorbornyl	USPAT;	2003/09/09 12:52
			US-PGPUB;	•
			EPO; JPO;	
23	4	\$10fluoronorbornyl	DERWENT USPAT;	2003/09/09 12:53
23	1	QTOTTGOTONOTBOTHYT	US-PGPUB;	2003/03/03 12:53
			EPO; JPO;	
			DERWENT	
24	3	\$10fluoroisobornyl	USPAT;	2003/09/09 12:54
			US-PGPUB;	•
			EPO; JPO; DERWENT	
25	2	\$10fluoroisobornyl not \$10fluoronorbornyl	USPAT;	2003/09/09 12:54
		•	US-PGPUB;	
1			EPO; JPO;	[
97	0.	au-13035-\$.did.	DERWENT	2002/00/00 12 45
97	"	au-13035-\$.d1d.	USPAT; US-PGPUB;	2003/09/09 13:46
			EPO; JPO;	
			DERWENT	
98	0	au-88013035-\$.did.	USPAT;	2003/09/09 13:46
			US-PGPUB;	
			EPO; JPO; DERWENT	•
-	1.	("20030008231").PN.	USPAT;	2003/09/09 10:02
			US-PGPUB;	
			EPO; JPO;	
	75	fl	DERWENT	2222/22/22 22 25
-	/5	fluorin\$8 near alicyclic	USPAT; US-PGPUB;	2003/09/08 10:25
			EPO; JPO;	
		·	DERWENT	
-	246	· · · · · · · · · · · · · · · · · · ·	USPAT;	2003/09/08 10:27
		acrylate)	US-PGPUB;	
			EPO; JPO; DERWENT	
-	247	(\$10octafluoropentyl adj (methacrylate	USPAT;	2003/09/09 12:11
		acrylate)) (\$10fluor\$10adamantyl adj	US-PGPUB;	
		(methacrylate acrylate)) and (resist	EPO; JPO;	
_	1	photoresist) \$10fluor\$10adamantyl adj (methacrylate	DERWENT	2002/00/00 11 15
-		acrylate)	USPAT; US-PGPUB;	2003/09/08 11:15
			EPO; JPO;	
			DERWENT	
-	4397	(fluorine fluoro fluorinated) near5	USPAT;	2003/09/08 16:21
		(methacrylate acrylate)	US-PGPUB;	
			EPO; JPO; DERWENT	
-	546	((fluorine fluoro fluorinated) near5	USPAT;	2003/09/08 10:36
		(methacrylate acrylate)) and (resist	US-PGPUB;	
,		photoresist)	EPO; JPO;	
1_	546	///fluoring fluoro fluoringted)	DERWENT	2002/00/00 24 25
1	546	(((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist	USPAT; US-PGPUB;	2003/09/08 14:06
		photoresist)) not (fluorin\$8 near alicyclic	EPO; JPO;	·
		)	DERWENT	
-	419	adamantyl adj (methacrylate acrylate)	USPAT;	2003/09/08 11:30
			US-PGPUB;	
			EPO; JPO;	
L	<u> </u>		DERWENT	

A 144				
[ -	0	(fluorine fluoro fluorinated) near	USPAT;	2003/09/08 11:16
		(adamantyl adj (methacrylate acrylate))	US-PGPUB; EPO; JPO;	
-	6990	cyclo\$5yl adj (methacrylate acrylate)	DERWENT USPAT;	2003/09/09 12:12
			US-PGPUB; EPO; JPO;	
_	0	2002363222.URPN.	DERWENT	2003/09/08 13:35
-	1	2001JP-0170197.prai.	USPAT; US-PGPUB;	2003/09/08 14:05
	904	fluoroalkyl near (methacrylate acrylate)	EPO; JPO; DERWENT USPAT;	2003/09/09 12:12
_	904	Truoroarkyr hear (methacryrate acryrate)	US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	868		USPAT;	2003/09/08 14:06
		not ((((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist	US-PGPUB; EPO; JPO;	
		photoresist)) not (fluorin\$8 near alicyclic	DERWENT	
-	5854256	s ((fluoroalkyl near (methacrylate acrylate)) not ((((fluorine fluoro	USPAT; US-PGPUB;	2003/09/08 14:07
		fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic ))) and (430/\$.ccls.)	EPO; JPO; DERWENT	
-	58		USPAT; US-PGPUB; EPO; JPO;	2003/09/08 14:08
		photoresist)) not (fluorin\$8 near alicyclic ))) and (430/\$.ccls.)	DERWENT	
-	12	fluorocycloalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO;	2003/09/08 14:19
		457	DERWENT	
-	44	\$fluorocyclo\$6yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO;	2003/09/08 15:27
	44	(\$fluorocyclo\$6yl adj (methacrylate	DERWENT USPAT;	2003/09/08 16:20
		acrylate)   not (fluorocycloalkyl near   (methacrylate acrylate)	US-PGPUB; EPO; JPO;	2003/03/08 10:20
-	302	alicyclic near (methacrylate acrylate)	DERWENT USPAT;	2003/09/08 16:20
			US-PGPUB; EPO; JPO;	
-	366		DERWENT USPAT;	2003/09/08 16:20
		(methacrylate acrylate)	US-PGPUB; EPO; JPO;	
-	12	(fluorine fluoro fluorinated) same	DERWENT USPAT;	2003/09/09 12:12
	-	((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )	US-PGPUB; EPO; JPO; DERWENT	·
-	17	(\$10fluorine \$10fluoro \$10fluorinated nonafluoro) same ((bicyclic polycyclic	USPAT; US-PGPUB;	2003/09/08 16:25
		alicyclic) near (methacrylate acrylate) )	EPO; JPO; DERWENT	

ENTER SCREEN EXPRESSION OR (END):end

Uploading C:\Program Files\Stnexp\Queries\10084828.str

STRUCTURE UPLOADED

=> que L1

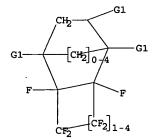
QUE L1

=> d

L2 HAS NO ANSWERS

L1

STR



G1 H, F, Ak, CF3

STD search Not Remove

Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L1

=> s 12 sss sam

SAMPLE SEARCH INITIATED 13:53:36 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 233 TO ITERATE

100.0% PROCESSED 233 ITERATIONS 0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:

ONLINE \*\*COMPLETE\*\* \*\*COMPLETE\*\* BATCH

PROJECTED ITERATIONS:

3745 TO

PROJECTED ANSWERS:

0 TO

L3 0 SEA SSS SAM L1

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END): end

=> screen 970 AND 2067

T.4 SCREEN CREATED

Uploading C:\Program Files\Stnexp\Queries\10084828-2.str

L5 STRUCTURE UPLOADED

=> crue L5 AND L4

L6 QUE L5 AND L4

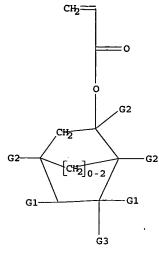
=> d

L6 HAS NO ANSWERS

L4 SCR 970 AND 2067

L5

STR



G1 H, F G2 H, F, CF3, Ak G3 F, CF2, CF3

Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L5 AND L4 L6

=> s 16 sss sam SAMPLE SEARCH INITIATED 13:54:27 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED -28 TO ITERATE

100.0% PROCESSED 28 ITERATIONS SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\* \*\*COMPLETE\*\* BATCH

243 TO

PROJECTED ITERATIONS:

PROJECTED ANSWERS: 0 TO 0

L7 O SEA SSS SAM L5 AND L4

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

Uploading C:\Program Files\Stnexp\Queries\10084828-3.str

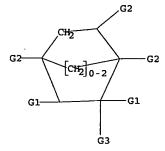
L8 STRUCTURE UPLOADED

=> que L8

L9 QUE L8

=> ' d

L9 HAS NO ANSWERS



G1 H, F

G2 H, F, CF3, Ak

G3 F, CF2, CF3

Structure attributes must be viewed using STN Express query preparation. L9 QUE ABB=ON PLU=ON L8

=> s 19 sss sam

SAMPLE SEARCH INITIATED 13:55:02 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED - 14330 TO ITERATE

7.0% PROCESSED 1000 ITERATIONS

1 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:

ONLINE \*\*COMPLETE\*\*
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS:

TH \*\*COMPLETE\*\* 279436 TO 293764

PROJECTED ANSWERS:

59 TO 513

L10

1 SEA SSS SAM L8

=> d

L10 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN

RN 195258-93-6 REGISTRY

CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yldifluoromethyl)-, diethyl ester,

exo- (9CI) (CA INDEX NAME)

FS STEREOSEARCH

MF C12 H21 F2 O3 P

SR CA

LC STN Files: CA, CAPLUS

Relative stereochemistry.

\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1937 TO DATE)

1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE TOTAL

ENTRY SESSION

FULL ESTIMATED COST

3.28 3.49

FILE 'HCAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

```
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FILE 'USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)
```

(FILE 'HOME' ENTERED AT 13:52:58 ON 08 SEP 2003)

FILE 'REGISTRY' ENTERED AT 13:53:06 ON 08 SEP 2003

L1 STRUCTURE UPLOADED L2 QUE L1 0 S L2 SSS SAM L3 SCREEN 970 AND 2067 L4 L5 STRUCTURE UPLOADED L6 QUE L5 AND L4 L7 0 S L6 SSS SAM STRUCTURE UPLOADED LS

QUE L8 1 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003

=> s 13 or 17 or 110 2 L3 OR L7 OR L10 L11

=> d l11 1-2 ibib hitstr

=> d his

L9

L11 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 HCAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a

(diethoxyphosphinoyl)difluoromethyl anion equivalent

to acyclic and cyclic vinyl sulfones

AUTHOR (S): Blades, K.; Lapotre, D.; Percy, J. M.

Sch. Chemistry, Univ. Birmingham, Edgbaston, Birmingham, B15 2TT, UK CORPORATE SOURCE:

SOURCE: Tetrahedron Letters (1997), 38(33), 5895-5898

CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier DOCUMENT TYPE: Journal

LANGUAGE: English 195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. of)

RN 195258-93-6 HCAPLUS

Phosphonic acid, (bicyclo[2.2.1]hept-2-yldifluoromethyl)-, diethyl ester, CN

exo- (9CI) (CA INDEX NAME)

Relative stereochemistry.

L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 CAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a

(diethoxyphosphinoyl)difluoromethyl anion equivalent

to acyclic and cyclic vinyl sulfones

AUTHOR (S): Blades, K.; Lapotre, D.; Percy, J. M.

Sch. Chemistry, Univ. Birmingham, Edgbaston, Birmingham, B15 2TT, UK CORPORATE SOURCE:

SOURCE: Tetrahedron Letters (1997), 38(33), 5895-5898

CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier DOCUMENT TYPE: Journal LANGUAGE: English

195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. of) RN 195258-93-6 CAPLUS CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yldifluoromethyl)-, diethyl ester, exo- (9CI) (CA INDEX NAME)

 ${\tt Relative \ stereochemistry}.$ 

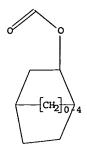
=> que L4

QUE L4 L5

=> d

L5 HAS NO ANSWERS

L4 STR



Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L4

=> s 15 sss sam

SAMPLE SEARCH INITIATED 14:03:26 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED - 17471 TO ITERATE

5.7% PROCESSED

1000 ITERATIONS

27 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*
BATCH \*\*COMPLETE\*\*

357325

PROJECTED ITERATIONS:

341515 TO 8131 TO 10737

PROJECTED ANSWERS:

27 SEA SSS SAM L4

L6

ANSWER 1 OF 27 REGISTRY COPYRIGHT 2003 ACS on STN L6

565462-43-3 REGISTRY RN

Bicyclo[2.2.1]heptane-2-carboxylic acid, 2-(benzoylamino)-3-CN

[(ethoxycarbonyl)oxy]-, ethyl ester, (1R, 2R, 3S, 4S)-rel- (9CI) (CA INDEX

NAME)

FS STEREOSEARCH

MF C20 H25 N O6

SR CA

STN Files: CA, CAPLUS

Relative stereochemistry.

\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1937 TO DATE)

1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE TOTAL

ENTRY SESSION

4.96 5.17

FULL ESTIMATED COST

```
FILE 'HCAPLUS' ENTERED AT 14:03:59 ON 08 SEP 2003
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FILE 'USPATFULL' ENTERED AT 14:03:59 ON 08 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)
=> s 16
Ь7
           139 L6
=> s 17 and (photoresist or resist)
            26 L7 AND (PHOTORESIST OR RESIST)
=> s 18 and (fluor?)
             7 L8 AND (FLUOR?)
=> duplicates remove 19
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L9
              6 DUPLICATE REMOVE L9 (1 DUPLICATE REMOVED)
=> d l10 1-6 ibib hitstr
L10 ANSWER 1 OF 6 USPATFULL on STN
ACCESSION NUMBER:
                        2003:126971 USPATFULL
TITLE:
                        Polymer, resist composition and patterning
                        process
INVENTOR(S):
                        Nishi, Tsunehiro, Niigata-ken, JAPAN
                        Hasegawa, Koji, Niigata-ken, JAPAN
Kinsho, Takeshi, Niigata-ken, JAPAN
                             NUMBER
                                          KIND
                                                   DATE
PATENT INFORMATION:
                        US 2003087183
                                                 20030508
                                           A1
APPLICATION INFO.:
                        US 2002-230341
                                            A1
                                                 20020829
                                                           (10)
                               NUMBER
                                             DATE
PRIORITY INFORMATION:
                        JP 2001-262833
                                            20010831
DOCUMENT TYPE:
                        Utility
FILE SEGMENT:
                        APPLICATION
LEGAL REPRESENTATIVE:
                        BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS
                        CHURCH, VA, 22040-0747
NUMBER OF CLAIMS:
                        4
EXEMPLARY CLAIM:
                        1
LINE COUNT:
                        1550
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT
    521950-67-4P
        (polymer and resist compn. for deep-UV and electron beam patterning
        process)
RN
     521950-67-4 USPATFULL
CN
     3,5-Methano-2H-cyclopenta[b] furan-7-carboxylic acid, hexahydro-2-oxo-6-[(1-
       oxo-2-propenyl)oxy]-, methyl ester, polymer with 2,5-furandione,
       2-methyltricyclo[3.3.1.13,7]dec-2-yl 2-propenoate and
       spiro[bicyclo[2.2.1]hept-5-ene-2,3'(2'H)-furan]-5'(4'H)-one (9CI) (CA
       INDEX NAME)
          1
     CM
     CRN 449759-66-4
     CMF C13 H14 O6
```

$$H_2C = CH - C - O$$
 $C - OMe$ 

CM

CRN 282542-79-4 CMF C10 H12 O2



CM

CRN 249562-06-9 CMF C14 H20 O2

CM

108-31-6 CRN CMF C4 H2 O3

L10 ANSWER 2 OF 6 USPATFULL on STN

ACCESSION NUMBER:

2003:10538 USPATFULL

TITLE:

Novel (meth) acrylates having lactone structure,

polymers, photoresist compositions and

patterning process

INVENTOR(S):

Kinsho, Takeshi, Niigata-ken, JAPAN

Hasegawa, Koji, Niigata-ken, JAPAN

PATENT ASSIGNEE(S):

Watanabe, Takeru, Niigata-ken, JAPAN Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S.

corporation)

NUMBER KIND DATE -----PATENT INFORMATION: US 2003008232 A1 20030109 APPLICATION INFO.: US 2002-167444 A1 20020613 (10)

NUMBER

PRIORITY INFORMATION:

DATE

DOCUMENT TYPE:

JP 2001-179614 20010614

Utility APPLICATION

FILE SEGMENT:

MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON LEGAL REPRESENTATIVE:

BLVD., SUITE 1400, ARLINGTON, VA, 22201

NUMBER OF CLAIMS: EXEMPLARY CLAIM:

8 1

LINE COUNT: 729 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 479072-45-2P

(lactone-contg. acrylate-based excimer laser-sensitive chem. amplified pos. photoresists with good transparency)

RN 479072-45-2 USPATFULL

2-Propenoic acid, dihydro-2'-oxospiro[bicyclo[2.2.1]heptane-2,3'(2'H)-furan]-6-yl ester (9CI) (CA INDEX NAME) CN

```
H<sub>2</sub>C=CH-C-O
```

```
L10 ANSWER 3 OF 6 HCAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER:
                         2002:868986 HCAPLUS
DOCUMENT NUMBER:
                         137:370796
TITLE:
                         Radiation-sensitive polysiloxane resin composition
INVENTOR(S):
                         Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu;
                         Yamamoto, Masafumi
                         JSR Co., Ltd., Japan
PCT Int. Appl., 155 pp.
PATENT ASSIGNEE(S):
SOURCE:
                         CODEN: PIXXD2
DOCUMENT TYPE:
                         Patent
LANGUAGE:
                         Japanese
FAMILY ACC. NUM. COUNT:
PATENT INFORMATION:
     PATENT NO.
                      KIND
                            DATE
                                            APPLICATION NO. DATE
     WO 2002090423
                            20021114
                                            WO 2002-JP4333
                                                             20020430
         W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
             CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
             GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT,
             LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,
             RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG,
             US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM
         RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH,
             CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR,
             BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
                                           JP 2002-48643
     JP 2003020335
                      A2
                            20030124
                                                             20020225
PRIORITY APPLN. INFO.:
                                         JP 2001-133795
                                                          Α
                                                             20010501
                                         JP 2002-48643
                                                          Α
                                                             20020225
OTHER SOURCE(S):
                         MARPAT 137:370796
     474559-57-4P
     RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP
     (Properties); PREP (Preparation); USES (Uses)
        (radiation-sensitive polysiloxane resin compn.)
     474559-57-4 HCAPLUS
CN
     Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-(triethoxysily1)-2-
     (trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 5(or
     6) - (triethoxysilyl) - .alpha., .alpha. -bis(trifluoromethyl)bicyclo[2.2.1]hept
     ane-2-ethanol and 5(or 6)-(triethoxysilyl)-2-(trifluoromethyl)bicyclo[2.2.
     1]hept-2-yl acetate (9CI) (CA INDEX NAME)
     CM .
     CRN
          474559-08-5
         C16 H27 F3 O5 Si
     CMF
     CCI
         IDS
      OAc
Eto-Si-OEt
     ÖEt
     CM
         474559-06-3
     CMF
         C19 H33 F3 O5 Si
     CCI
         IDS
```

CM 3

CRN 365546-74-3 CMF C17 H28 F6 O4 Si CCI IDS

REFERENCE COUNT:

25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 4 OF 6 USPATFULL on STN

ACCESSION NUMBER:

2002:119480 USPATFULL TITLE: Polymer, resist composition and patterning

process

INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN

Nakashima, Mutsuo, Nakakubiki-gun, JAPAN Tachibana, Seiichiro, Nakakubiki-gun, JAPAN Kinsho, Takeshi, Nakakubiki-gun, JAPAN

Hasegawa, Koji, Nakakubiki-gun, JAPAN Watanabe, Takeru, Nakakubiki-gun, JAPAN Hatakeyama, Jun, Nakakubiki-gun, JAPAN

Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. PATENT ASSIGNEE(S):

corporation)

NUMBER KIND DATE US 2002061463 20020523 A1

PATENT INFORMATION: APPLICATION INFO.:

US 2001-951523 A1 20010914

NUMBER DATE JP 2000-279164

PRIORITY INFORMATION:

20000914

DOCUMENT TYPE: Utility FILE SEGMENT:

APPLICATION

LEGAL REPRESENTATIVE: MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON

BLVD., SUITE 1400, ARLINGTON, VA, 22201

NUMBER OF CLAIMS: 7 EXEMPLARY CLAIM: LINE COUNT: 1766

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 409093-65-8P

(polymers with cyclopentane rings in or adjacent to the chains for

resists patternable by UV or electron beams)

409093-65-8 USPATFULL

2-Propenoic acid, 2-methyl-, 2-ethylbicyclo[2.2.1]hept-2-yl ester, polymer CN with 5-(2-bicyclo[2.2.1]hept-5-en-2-ylethyl)dihydro-2(3H)-furanone and 2,5-furandione (9CI) (CA INDEX NAME)

CRN 370089-03-5 CMF C13 H18 O2

CM

CRN 330595-98-7 CMF C13 H20 O2

CM

108-31-6 CRN CMF C4 H2 O3

INVENTOR(S):

L10 ANSWER 5 OF 6 USPATFULL on STN

ACCESSION NUMBER:

2001:147641 USPATFULL

TITLE:

Ester compounds, polymers, resist compositions and patterning process Kinsho, Takeshi, Nakakubiki-gun, Japan

Nishi, Tsunehiro, Nakakubiki-gun, Japan Kurihara, Hideshi, Usui-gun, Japan Nakashima, Mutsuo, Nakakubiki-gun, Japan Hasegawa, Koji, Nakakubiki-gun, Japan Watanabe, Takeru, Nakakubiki-gun, Japan

PATENT ASSIGNEE(S):

Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S.

corporation)

NUMBER KIND DATE

PATENT INFORMATION: APPLICATION INFO.:

US 6284429 B1 20010904 US 2000-512108 20000224

NUMBER

DATE

PRIORITY INFORMATION:

JP 1999-47406 19990225 JP 1999-174945 19990622

DOCUMENT TYPE:

Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Ashton, Rosemary E.

LEGAL REPRESENTATIVE: Millen, White, Zelano & Branigan, P.C

NUMBER OF CLAIMS: 19

1

EXEMPLARY CLAIM: LINE COUNT:

2016

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 290808-37-6P

(novel ester compds., polymers, resist compns. and patterning process)

290808-37-6 USPATFULL

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (1R,2S,4S)-2-(1-

methylethyl)bicyclo[2.2.1]hept-2-yl ester, rel- (9CI) (CA INDEX NAME)

Relative stereochemistry.

L10 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER:

2001:142042 USPATFULL

TITLE:

Lactone-containing compounds, polymers, resist

INVENTOR(S):

compositions, and patterning method Hasegawa, Koji, Nakakubiki-gun, Japan Nishi, Tsunehiro, Nakakubiki-gun, Japan Kinsho, Takeshi, Nakakubiki-gun, Japan Hatakeyama, Jun, Nakakubiki-gun, Japan

PATENT ASSIGNEE(S):

Watanabe, Osamu, Nakakubiki-gun, Japan Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S.

DATE

(9)

corporation)

NUMBER KIND

PATENT INFORMATION: APPLICATION INFO.:

US 6280898 В1 20010828 US 1999-404763 19990924

NUMBER

DATE

PRIORITY INFORMATION:

JP 1998-270373 19980925

DOCUMENT TYPE:

Utility

FILE SEGMENT:

GRANTED

PRIMARY EXAMINER:

Baxter, Janet Ashton, Rosemary

ASSISTANT EXAMINER: LEGAL REPRESENTATIVE:

Millen, White, Zelano & Branigan, P.C.

NUMBER OF CLAIMS: EXEMPLARY CLAIM:

21 1

LINE COUNT:

1654

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 274248-37-2P

(synthesis of lactone-contg. polymers for resist compns. and method of forming resist pattern using the compn.)

274248-37-2 USPATFULL

CN

RN

2-Propenoic acid, 2-methyl-, octahydro-7-(1-methylethyl)-2-oxo-3,6methanobenzofuran-7-yl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 274248-01-0 CMF C16 H22 O4

CM

52858-59-0 CRN C9 H14 O3 CMF

=> d his (FILE 'HOME' ENTERED AT 10:15:29 ON 09 SEP 2003) FILE 'REGISTRY' ENTERED AT 10:15:44 ON 09 SEP 2003 SCREEN 963 AND 970 AND 1006 AND 2067 Ll STRUCTURE UPLOADED L2 L3 QUE L2 AND L1 15 S L3 SSS SAM L4 FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 10:17:00 ON 09 SEP 2003 1.5 69 S L4 L6 9 S L5 AND (FLUORINE OR FLUORINATED OR FLUORO) 1.7 8 DUPLICATE REMOVE L6 (1 DUPLICATE REMOVED) => d 17 1-8 ibib L7 ANSWER 1 OF 8 USPATFULL on STN ACCESSION NUMBER: 2003:106118 USPATFULL TITLE: Positive-working resist composition INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN Kodama, Kunihiko, Shizuoka, JAPAN Aoai, Toshiaki, Shizuoka, JAPAN PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation) KIND DATE NUMBER US 2003073029 A1 20030417 PATENT INFORMATION: A1 20011220 (10) APPLICATION INFO.: US 2001-22363 RELATED APPLN. INFO.: Division of Ser. No. US 2000-684888, filed on 6 Oct 2000, PENDING NUMBER DATE PRIORITY INFORMATION: JP 1999-285761 19991006 JP 2000-80519 20000322 DOCUMENT TYPE: Utility FILE SEGMENT: APPLICATION LEGAL REPRESENTATIVE: SUGHRUE MION, PLLC, 2100 Pennsylvania Avenue, NW, Washington, DC, 20037-3213 NUMBER OF CLAIMS: 10 EXEMPLARY CLAIM: LINE COUNT: 2718 CAS INDEXING IS AVAILABLE FOR THIS PATENT. ANSWER 2 OF 8 USPATFULL on STN ACCESSION NUMBER: 2003:23576 USPATFULL TITLE: Positive photosensitive composition INVENTOR(S): Kodama, Kunihiko, Shizuoka, JAPAN Sato, Kenichiro, Shizuoka, JAPAN PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation) KIND NUMBER DATE -----PATENT INFORMATION: US 2003017415 A1 20030123 APPLICATION INFO.: US 2002-79414 A1 20020222 (10) NUMBER DATE PRIORITY INFORMATION: JP 2001-48602 20010223 JP 2001-48783 20010223 JP 2001-48784 20010223 JP 2001-48880 20010223 JP 2001-157366 20010525 JP 2001-157367 20010525 DOCUMENT TYPE: Utility FILE SEGMENT: APPLICATION LEGAL REPRESENTATIVE: SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W., WASHINGTON, DC, 20037 NUMBER OF CLAIMS: 19 EXEMPLARY CLAIM: 1 LINE COUNT: 3838 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 . ANSWER 3 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:17287 USPATFULL

TITLE:

Resist composition and patterning process Kobayashi, Tomohiro, Niigata-ken, JAPAN INVENTOR(S): Nishi, Tsunehiro, Niigata-ken, JAPAN

Watanabe, Satoshi, Niigata-ken, JAPAN Kinsho, Takeshi, Niigata-ken, JAPAN Nagura, Shigehiro, Niigata-ken, JAPAN

Ishihara, Toshinobu, Niigata-ken, JAPAN

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, UNITED STATES, 100-0004 (non-U.S. corporation)

NUMBER KIND DATE

PATENT INFORMATION: US 2003013039 A1 20030116 APPLICATION INFO.: US 2002-170345 20020614 (10) A1

> NUMBER DATE

PRIORITY INFORMATION: JP 2001-181079 20010615

DOCUMENT TYPE: Utility

FILE SEGMENT: APPLICATION

LEGAL REPRESENTATIVE: MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON

BLVD., SUITE 1400, ARLINGTON, VA, 22201

NUMBER OF CLAIMS: EXEMPLARY CLAIM: 1

LINE COUNT: 1854

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

ANSWER 4 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:209927 USPATFULL

Positive-working resist composition TITLE: INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN Kodama, Kunihiko, Shizuoka, JAPAN Aoai, Toshiaki, Shizuoka, JAPAN

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.

corporation)

NUMBER KIND DATE PATENT INFORMATION: US 6602646 B1 20030805 APPLICATION INFO.: US 2000-684888 20001006 (9)

NUMBER DATE PRIORITY INFORMATION: JP 1999-285761 19991006

JP 2000-80519 DOCUMENT TYPE:

Utility

20000322

FILE SEGMENT: GRANTED PRIMARY EXAMINER:

Ashton, Rosemary LEGAL REPRESENTATIVE: Sughrue Mion, PLLC NUMBER OF CLAIMS:

EXEMPLARY CLAIM:

NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)

LINE COUNT: 2562

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

ANSWER 5 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:197025 USPATFULL

TITLE: Positive-working photoresist composition INVENTOR (S): Sato, Kenichiro, Shizuoka, JAPAN

Kodama, Kunihiko, Shizuoka, JAPAN Aoai, Toshiaki, Shizuoka, JAPAN Kawabe, Yasumasa, Shizuoka, JAPAN

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.

corporation)

KIND DATE NUMBER US 6596458 B1 20030722 PATENT INFORMATION: B1 20030722 APPLICATION INFO.: US 2000-563436 20000503 (9)

NUMBER DATE PRIORITY INFORMATION: JP 1999-127296 19990507 JP 1999-186607 19990630 JP 1999-193601 19990707 JP 1999-193602 19990707 JP 1999-193603 19990707

DOCUMENT TYPE: Utility FILE SEGMENT: GRANTED PRIMARY EXAMINER: Chu, John S.

LEGAL REPRESENTATIVE: Sughrue Mion, PLLC

NUMBER OF CLAIMS: 8 EXEMPLARY CLAIM: 1

NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)

LINE COUNT: 1613

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

ANSWER 6 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2002:272716 USPATFULL

TITLE: Polymer, resist composition and patterning process

INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN Nakashima, Mutsuo, Nakakubiki-gun, JAPAN Tachibana, Seiichiro, Nakakubiki-gun, JAPAN

Funatsu, Kenji, Nakakubiki-gun, JAPAN

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S.

corporation)

NUMBER KIND DATE ----- ----A1 20021017 A1 20020213 (10) PATENT INFORMATION: US 2002150835 APPLICATION INFO : US 2002-73223

NUMBER DATE PRIORITY INFORMATION: JP 2001-37247 20010214 JP 2001-37262 20010214 JP 2001-37271 20010214

DOCUMENT TYPE: Utility FILE SEGMENT: APPLICATION

LEGAL REPRESENTATIVE: MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON

BLVD., SUITE 1400, ARLINGTON, VA, 22201

NUMBER OF CLAIMS: 4 EXEMPLARY CLAIM: LINE COUNT: 1682

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2001:143826 CAPLUS

DOCUMENT NUMBER: 134:200525

TITLE: Positive-working photoresist composition for far

INVENTOR(S):

ultraviolet ray exposure
Aogo, Toshiaki; Sato, Kenichiro; Kodama, Kunihiko
Fuji Photo Film Co., Ltd., Japan PATENT ASSIGNEE(S): SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE ---------------JP 2001056557 A2 20010227 JP 1999-234240 19990820 PRIORITY APPLN. INFO.: JP 1999-234240

ANSWER 8 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2001:212076 USPATFULL

TITLE:

Chemically amplified positive resist composition INVENTOR(S): Uetani, Yasunori, Osaka, Japan

Yamada, Airi, Osaka, Japan Miya, Yoshiko, Muko-shi, Japan Takata, Yoshiyuki, Osaka, Japan

NUMBER KIND DATE -----PATENT INFORMATION: A1 US 2001044070 20011122 US 6579659

B2 20030617 A1 20010403 (9) APPLICATION INFO.: US 2001-824227

NUMBER DATE JP 2000-101868 PRIORITY INFORMATION: 20000404

JP 2000-133328 20000502 JP 2000-209505 20000711

DOCUMENT TYPE: Utility

FILE SEGMENT: APPLICATION

LEGAL REPRESENTATIVE: BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS

CHURCH, VA, 22040-0747

NUMBER OF CLAIMS: 5 EXEMPLARY CLAIM: 1 LINE COUNT: 894

CAS INDEXING IS AVAILABLE FOR THIS PATENT.